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D. BELL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

CMZ 10/27/02

Applicants: SCHULTZ ET AL.
Serial No: 09/627,559
For: ILLUMINATION SYSTEM WITH A PLURALITY OF LIGHT SOURCES
Filed: JULY 27, 2000
Examiner: BERNARD E. SOUW
Art Unit: 2881 Docket No.: 637.0003USU

AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

Applicants are submitting the present document in response to an Office Action dated June 27, 2002. Please amend the above-noted application as follows:

IN THE SPECIFICATION

Please amend the portions of the Specification identified below to read as indicated herein. A version of the amended portions of the Specification with markings to show changes made is included at the end of this document.

Page 3, paragraph starting at line 26

B1

If the numerical aperture in the plane of the wafer is in the range $NA_{wafer} = 0.1-0.25$ then in the case of 4:1 systems, a numerical aperture in the reticle plane of $NA_{reticle} = 0.025$

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